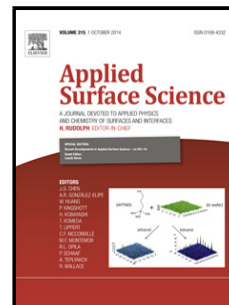


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Title: Temporal evolution of the chemical structure during the pattern transfer by ion-beam sputtering

Author: N.-B. Ha S. Jeong S. Yu H.-I. Ihm J.-S. Kim



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Highlight

- Chemical analyses of the individual nano structures simultaneously with the investigation of their morphological evolution were performed.
- Degradation of the transferred pattern starts before the overlayer is fully removed.
- The chemical analysis reveals the severe reduction of the sputter yield of the material forming the overlayer near the interface due to the compound formation, requesting caution in the practice of the pattern transfer.

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